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# REQUEST FOR CONTINUED EXAMINATION (RCE) TRANSMITTAL

Address to:  
Commissioner for Patents  
BOX RCE  
Washington, DC 20231

Application No.	09/600,546
Filing Date	July 12, 2000
First Named Inventor	Claude Chappert
Group Art Unit	1756
Examiner Name	Angebranndt, M.J.
Attorney Docket Number	15675P322

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## This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application.

Request for Continued Examination (RCE) practice under 37 CFR § 1.114 does not apply to any utility or plant application filed prior to June 8, 1995, or to any design application. See Instruction Sheet for RCEs (not to be submitted to the USPTO) on page 2.

### 1. Submission required under 37 C.F.R. § 1.114

- a. ☐ Previously submitted
- i. ☐ Consider the amendment(s)/reply under 37 C.F.R. § 1.116 previously filed on  
(Any unentered amendment(s) referred to above will be entered).
- ii. ☐ Consider the arguments in the Appeal Brief or Reply Brief previously filed on
- iii. ☐ Other \_\_\_\_\_
- b. ☒ Enclosed
- i. ☐ Amendment/Reply
- ii. ☐ Affidavit(s)/Declaration(s)
- iii. ☐ Information Disclosure Statement (IDS)
- iv. ☒ Other **Preliminary Amendment**

### 2. Miscellaneous

- a. ☐ Suspension of action on the above-identified application is requested under 37 C.F.R. § 1.103(c) for a period of \_\_\_\_\_ months. (Period of suspension shall not exceed 3 months; Fee under 37 C.F.R. § 1.17(i) required)
- b. ☐ Other \_\_\_\_\_

### 3. Fees

The RCE fee under 37 C.F.R. § 1.17(e) is required by 37 C.F.R. § 1.114 when the RCE is filed.

- a. ☒ The Director is hereby authorized to charge the following fees, or credit any overpayments, to Deposit Account No. 02-2666.
- i. ☒ RCE fee required under 37 C.F.R. § 1.17(e)
- ii. ☒ Extension of time fee (37 C.F.R. § 1.136 and 1.17)
- iii. ☐ Other: (\$00) \_\_\_\_\_
- b. ☒ Check in the amount of \$1,680.00 enclosed
- c. ☐ Payment by credit card (Form PTO-2038 enclosed)

**WARNING: Information on this form may become public. Credit card information should not be included on this form. Provide credit card information and authorization on PTO-2038.**

### SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED

Name (Print/Type)	Walter T. Kim	Registration No. (Attorney/Agent)	42,731
Signature	<i>Walter T. Kim</i>	Date	January 8, 2003

### CERTIFICATE OF MAILING OR TRANSMISSION

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class mail with sufficient postage in an envelope addressed to: Box RCE, Assistant Commissioner for Patents, Washington, D.C. 20231 on:

January 8, 2003

Name (Print/Type)	Linda D'Elia	Date	January 8, 2003
Signature	<i>Linda D'Elia</i>		

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Attorney Docket No. 015675.P322

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Patent Application of:

CLAUDE CHAPPERT

Serial No. 09/600,546

Filed: July 12, 2000

For: **MAGNETIC ETCHING PROCESS,  
ESPECIALLY FOR MAGNETIC OR  
MAGNETOOPTIC RECORDING**

Examiner: Angebranndt, Martin J.

Art Unit: 1756

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**PRELIMINARY AMENDMENT**

Box RCE  
Commissioner for Patents  
Washington, D.C. 20231-9998

Dear Sir:

In connection with the RCE (Request for Continued Examination) filed herewith regarding the above-referenced application, Applicant respectfully requests consideration of the following amendments and remarks.

**IN THE CLAIMS**

**Please amend Claim 1 as follows:**

1. (Amended) A writing process for forming a pattern on a multi-layer material composed of thin layers deposited on a substrate, in which said multi-layer material is irradiated by means of a beam of light ions, having an energy of the order of or less than a hundred keV, wherein one or more regions of the multi-layer material having individual sizes of the order of 1 micrometer or less are selectively irradiated, the irradiation dose being controlled so as to be a few  $10^{16}$  ions/cm<sup>2</sup> or less, the irradiation